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Substitute for form 1449B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT Date Submitted: AUG 22 2003 (use as many sheets as necessary)				Complete if Known	
Sheet	1	of	1	Application Number	Unassigned 2 2003
				Filing Date	AUG 22 2003
				First Named Inventor	Hisatsugu KURITA
				Group Art Unit	Unassigned
				Examiner Name	Unassigned
				Attorney Docket Number	047297-0137

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
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FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No. ¹	Foreign Patent Document		Name of Patentee or Applicant of Cited Documents	Date of Publication of Cited Document MM-DD-YYYY		
		Office ³	Number ⁴	Kind Code ⁵ (if known)	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
MK	A1	JP	10-340876	A	SHIBAURA ENG WORKS CO., LTD.	12-22-1998	✓

NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.			
MK	A2	S. VERHAVERBEKE et al., "THE EFFECT OF H ₂ ANNEALING ON THE SI SURFACE AND ITS USE IN THE STUDY OF ROUGHENING DURING WET CHEMICAL CLEANING", Semiconductor Silicon, 1994, pages 1170-1181, vol. 94-no. 10, The Electrochemical Society, Inc.			
MK	A3	Y. YANASE et al., "AFM OBSERVATION OF Si(100) SURFACE AFTER HYDROGEN ANNEALING AND WET CHEMICAL PROCESSING", Electrochemical Society 184 th Meeting, Third international symposium on Cleaning Technology in Semiconductor Device Manufacturing, Oct. 10-15, 1993, 8 pages			

Examiner Signature		Date Considered	03/03/05
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document.

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